

Amendments to the Drawings:

The attached sheets labeled "Replacement Sheet" include changes to FIGS. 2 to 4.

In the amended FIG. 2, a legend of --(Prior Art)-- is added.

5 In the amended FIG. 3, the lower symbol 54 is changed to "52" to represent the cleaning mechanism, and symbol 55 is added to represent the sucking port of the vacuuming pump 54. One of ordinary skill in the art may easily understand that a vacuuming pump has a sucking port according to the arrow depicted in the vacuuming pump 54 of FIG. 3. So, no new matter is added.

10 In the amended FIG. 4, symbol 50A is added to represent the upper portion of the sealed up body 50, symbol 55 is added in a manner similar to that of FIG. 3, and symbol 62 is added to represent the cleaning room, which has been labeled in FIG. 3. In addition, two line segments are added to separate the substrate 64 from the frame layer 66 in a manner similar to that in FIG. 2, wherein the substrate
15 10 is separated from the frame layer 18. So, no new matter is added.

REMARKS/ARGUMENTS

The title, the specification, the abstract and drawings have been correspondingly amended without adding new matter and will be explained as
5 below.

In the title of the invention, a new title "CLEANING SYSTEM HAVING A COMBINATION OF A SUBSTRATE AND A FRAME LAYER BEING CLEANED BY A CLEANER EJECTED SLANTINGLY UPWARDS" is given.

In the specification and abstract, the changes include the following features
10 without adding new matter.

1. The "cleaning mechanism" is changed to the suitable "cleaning system".

2. Some grammar and usage errors are corrected.

3. The combination of the substrate and the frame layer of FIG. 4 is defined as an object to be cleaned.

15 4. The periphery wall 58 is connected to the lower element 56, and the upper cover 60 is connected to the periphery wall 58 to form a cleaning room 62. This feature has been clearly shown in the original FIGS. 3 and 4.

5. The substrate 64 is disposed in the cleaning room 62 and fixed to an upper portion 50A of the sealed up body 50 with the chamber 68 facing downwards.
20 These features have been clearly shown in the original FIG. 4.

6. The cleaning mechanism 52 is disposed in the cleaning room 62 of the sealed up body 50 and ejects a cleaner slantingly upwards to clean the chamber 68 of the combination of the substrate 64 and the frame layer 66. These features have been clearly shown in the original drawing.

25 7. The vacuuming pump 54 is disposed in the cleaning room 62 and under the chamber 68 of the combination of the substrate 64 and the frame layer 66. This feature has been clearly shown in the original drawing.

8. Two cleaning mechanisms 52 are disposed opposite to each other. This feature has been clearly shown in the original drawing.

30 9. The vacuuming pump 54 has a sucking port 55 for sucking the cleaner, and

the sucking port 55 is disposed between the cleaning mechanisms 52.

Claims 1-7 are now present in this application. Claims 1-5 have been amended according to the amended specification and FIGS. 3 and 4. Claims 6-7
5 have been added.

Claim rejections – 35 U.S.C. 112

Claim 1 is rejected under 35 U.S.C. 112.

In response to the rejection, claims 1 to 5 have been amended to overcome
10 the problems of grammatical and idiomatic errors, the insufficient antecedent basis, and the “end” and seal up body” in claim 1.

Claim rejections – 35 U.S.C. 102

The examiner rejects claims 1-4 under 35 U.S.C. 102(b) as being anticipated
15 by Paranjpe (US 5494526).

Claim 1 has been amended to state that:

the cleaning system includes a combination of a substrate and a frame layer arranged on the substrate to form a chamber together with the substrate;

the substrate is disposed in the cleaning room and fixed to an upper portion
20 of the sealed up body with the chamber facing downwards; and

the first cleaning mechanism is disposed in the cleaning room of the sealed up body and ejects a cleaner slantingly upwards to clean the chamber of the combination of the substrate and the frame layer.

25 Paranjpe does not teaches that:

the cleaning system includes a combination of a substrate and a frame layer arranged on the substrate to form a chamber together with the substrate;

the substrate is disposed in the cleaning room and fixed to an upper portion of the sealed up body with the chamber facing downwards; and

30 the first cleaning mechanism is disposed in the cleaning room of the sealed

up body and ejects a cleaner slantingly upwards to clean the chamber of the combination of the substrate and the frame layer.

In fact, Paranjpe teaches that the cleaning agent (34) is initially in a liquid phase and is caused to change to a vapor phase so that the cleaning agent (34) can
5 penetrate the topography of the surface to be cleaned (see Abstract). Thus, the cleaning agent (34) is not ejected slantingly upwards but is vaporized upwards.

Considerations of the amended claim 1 and its dependent claims 2-4 are therefore politely requested.

10 **Claim rejections – 35 U.S.C. 102**

The examiner rejects claim 5 as being unpatentable over Paranjpe.

Since claim 1 has been amended. Consideration of the amended claim 5 is therefore politely requested.

15 In light of the above-mentioned amendments and remarks, Applicant now asserts that all of the grounds for rejections have been traversed or overcome by amendments, and that all of the present claims are in condition for immediate allowance. Applicant therefore requests reconsideration of the rejections and objections, and solicits allowance of the present claims at an early date.

20 Thank you for your consideration.

Respectfully submitted,

Date: March 5, 2007 